Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	piezoelectric near2 (flow adj regulator\$1)	US-PGPUB; USPAT	OR	ON	2005/12/16 15:28
L2	555	piezoelectric near2 flow	US-PGPUB; USPAT	OR	ON	2005/12/16 15:29
L3	399	piezoelectric near2 (controller\$1 or regulator\$1)	US-PGPUB; USPAT	OR	ON	2005/12/16 15:30
L4	14038	deposition adj (chamber or reactor)	US-PGPUB; USPAT	OR	ON	2005/12/16 15:30
L5	3452758	second	US-PGPUB; USPAT	OR	ON	2005/12/16 15:30
L6	7	I3 and I4 and I5	US-PGPUB; USPAT	OR	ON	2005/12/16 16:36
L7	61	I5 near source near chemical	US-PGPUB; USPAT	OR	ON	2005/12/16 17:25
L8	0	12 and 17	US-PGPUB; USPAT	OR	ON	2005/12/16 17:25
L9	25885	flow near (controller\$1 or regulator\$1)	US-PGPUB; USPAT	OR	ON	2005/12/16 17:25
L10	9	17 and 19	US-PGPUB; USPAT	OR	ON	2005/12/16 17:26